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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Not for submission under 37 CFR 1.99)	Application Number		10518060
	Filing Date		2005-06-09
	First Named Inventor	Lutz Lehmann	
	Art Unit	1712	
	Examiner Name	Kua Liang Peng	
	Attorney Docket Number	H26787.68596 US - 4780	

U.S. PATENTS

Examiner Initial*	Cite No	Patent Number	Kind Code ¹	Issue Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
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	8	4935583		1990-06-19	Kyle, James C.	

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22	5674648	A	1997-10-07	Brewer et al.	
23	4191571		1980-03-04	Nonogaki et al.	

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	1	20060110682	A1	2006-05-25	Shipley Company, L.L.C.	
	2	20060155594	A1	2006-07-13	Jess Almeida, et al.	

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	1	Crivello et al., J. Polym. Sci.: Polym. Chem. 21 (1983), 97-109.	<input type="checkbox"/>
	2	Degussa, "Silanes for Adhesives and Sealants," 18-19, available at www.dynasylan.com.	<input type="checkbox"/>
	3	Lamola, A. et al., "Chemically Amplified Resists," Solid State Technology, 53-60 (August 1991).	<input type="checkbox"/>
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11	Jaskot et al., Toxicological Sciences, 22(1): 103-112 (1994).	<input type="checkbox"/>
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14	Yusuke Izumi et al., "Hydrosilylation of Carbonyl Compounds Catalyzed by Solid Acids and Bases," Tetrahedron Letters, Vol. 32, No. 36, pp 4744 (1991).	<input type="checkbox"/>

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